

Amendments to the Specifications

Page 1 (Title)

~~METHOD FOR FABRICATING 3-D STRUCTURES WITH SMOOTHLY-VARYING~~
~~TOPOGRAPHICAL FEATURES IN PHOTO-SENSITIVE EPOXY RESISTS~~

Page 6, Line 1:

The present invention comprises ~~a new process by which~~ 3-D structures with smoothly-varying topographic features and continuously-varying thickness which can be fabricated by using one layer of photo-sensitized epoxy resist and a one exposure and development process sequence. The structures are formed in a layer of photo-sensitized epoxy resist having an initial selected thickness residing on a substrate, by exposing said layer, comprising a material such as SU-8, to doses of UV light which impinge on said layer from the substrate side, said doses varying across the width and breadth of the surface of said substrate.